

Title (en)
SEMICONDUCTOR PACKAGE, SEMICONDUCTOR DEVICE, ELECTRONIC DEVICE, AND METHOD OF MANUFACTURING SEMICONDUCTOR PACKAGE

Title (de)
HALBLEITERGEHÄUSE, HALBLEITER, ELEKTRONIKELEMENT UND HERSTELLUNG EINES HALBLEITERGEHÄUSES

Title (fr)
BOITIER A SEMI-CONDUCTEUR, DISPOSITIF SEMI-CONDUCTEUR, DISPOSITIF ELECTRONIQUE ET PROCEDE DE FABRICATION DE BOITIER A SEMI-CONDUCTEUR

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Application
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Priority
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Abstract (en)
[origin: EP1107307A1] An insulating layer (3) having an opening portion (3a) at a position conformable to an electrode pad (2) is formed. Next, a resin projection portion (4) is formed on the insulating layer (3). Thereafter, a resist film is formed which has opening portions made in regions conformable to the opening portion (3a), the resin projection portion (4) and the region sandwiched therebetween. A Cu plating layer (6) is formed by electrolytic copper plating, using the resist film as a mask. <IMAGE>

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H01L 21/60; H01L 23/12

IPC 8 full level
H01L 21/56 (2006.01); **H01L 23/31** (2006.01); **H01L 23/485** (2006.01); **H01L 23/525** (2006.01)

CPC (source: EP US)

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